

Calipso

Center for surface analytical services

Expertise center for High Sensitivity Low Energy Ion Scattering (HS-LEIS)

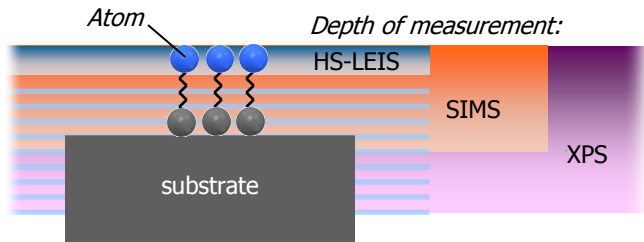
Activities of Calipso

Calipso provides chemical analysis of the outermost layer of atoms on a material. These measurements are performed with unique HS-LEIS equipment. An understanding of the outermost atomic layer is important since this layer defines the properties of the surface, such as adhesion and wetting properties, and the activity of a catalyst.



A HS-LEIS instrument at Calipso

HS-LEIS compared to SIMS and XPS:



schematic representation of cross section of surface

HS-LEIS - quantitative 1st atomic layer

- in-depth profile 0-10 nm (shaded area)

SIMS

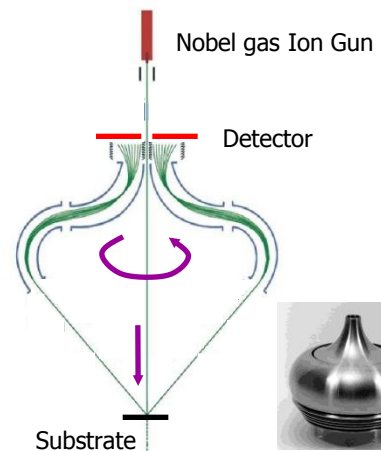
- not quantitative (for 1st atomic layer)

- chemical information

XPS

- information depth of 3 – 10 nm

Unique HS-LEIS analyzer:



Picture of analyzer

Unique features of HS-LEIS:

- Quantitative and highly sensitive measurement of outermost atomic surface layer
- Accurate surface analyses on samples with rough surface
- Analysis on non-conductive materials
- Choice of pretreatment and temperature during analysis

Areas of applications:

- Catalysis
- Coatings
- Diffusion Barriers
- Adhesion
- Corrosion
- Biocompatibility etc.

Materials:

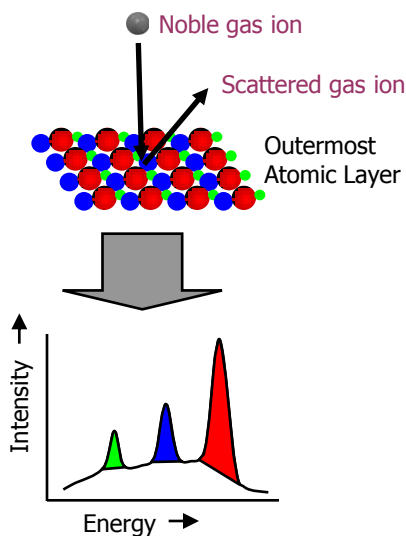
- Catalysts
- Metals
- Polymers
- Ceramics
- Biomaterials etc.

For details contact:

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Types of analyses possible with HS-LEIS

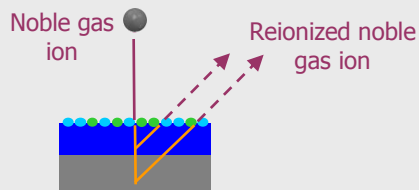
Measurement of composition



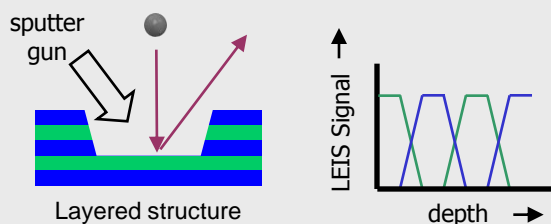
Energy spectrum of the scattered ions

Measurement of depth profile

Non-destructive (0-10 nm)

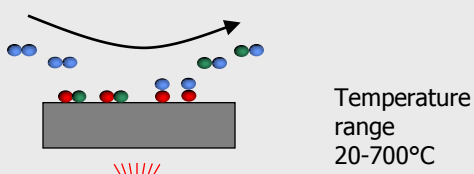


Destructive (large depths)

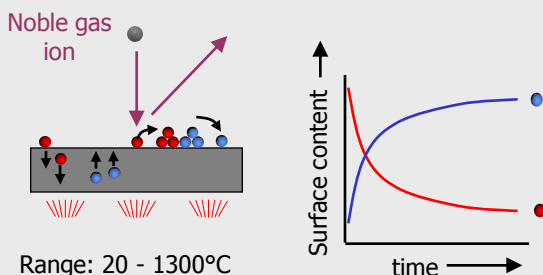


In-situ treatments

Chemical and/or heat treatment in pre-chamber



Heat treatment in combination with analysis



Range: 20 - 1300°C

Features of HS-LEIS

- | | | |
|--------------------------|---|--|
| 1. Monolayer sensitivity | Li - O
F - Cl
K - U | few % - 1 %
1 % - 0.05 %
0.05 % - 10 ppm |
| 2. Mass separation | isotopes elements possible | ¹⁶ O / ¹⁸ O, ⁶³ Cu / ⁶⁵ Cu
Al / Si, Ag / Pd |
| 3. Ion dose | < 1.10 ¹³ He ions/cm ² for polymers | |
| 4. Lateral resolution | 0.01 - 0.5 mm | |
| 5. In depth | 0-10 nm | |

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